

L Number	Hits	Search Text	DB	Time stamp
1	0	6602620.pn. and block with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/06 12:35
-	1396	mask with pattern with magnetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 13:57
-	325	((mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/06 10:00
-	102	((mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:42
-	107	((mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:43
-	0	mask with pattern with magnetic same layer with record\$3 and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:45
-	0	mask with pattern with magnetic same layer and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:44
-	0	mask with pattern with magnetic same layer and pholithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:44
-	0	mask with pattern with magnetic and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:45
-	0	mask with pattern with magnetic and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:46
-	1117	mask with pattern with magnetic and (pholithography and plasma etch\$3 lithography)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:47
-	62	mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:49
-	18	((mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:50

-	10	((mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:55
-	10	((mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:56
-	9	(mask with pattern with magnetic same layer and (pholithography same plasma plasma same etch\$3 and lithography same etch\$3)) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/06 10:01
-	75	(mask with pattern with magnetic same layer and (pholithography same plasma plasma same etch\$3 lithography same etch\$3)) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/06 12:34